

## ABSTRACT:

The minimal feature width (CD) of a pattern of device features configured in a substrate layer by means of a lithographic process can be reduced considerably, without reducing process latitudes (DOF), by substantially extending the post-exposure bake step and reducing the exposure dose. By the same measures the isofocal CD can be tuned to the design

5 CD so that for an arbitrary CD process latitudes are enlarged.

Fig. 2